Date:

May 3, 2002

AMENDMENTAND RESPONSE

Filea:

Sir:

This is a amendment in the above-identified application and includes the herewith attachment of same date and subject which is incorporated hereinto by reference and the signature below is treated as the signature to the attachment in absence of a signature thereto.

FEE REQUIREMENTS FOR CLAIMS AS AMENDED

	I EE KEGOII	TEIVEDITIO :	<u> </u>				
1. Small Entity claim A. \(\begin{align*} \begin{align*} \text{NOT} \\ \text{made} \\ \text{B.} \(\begin{align*} \text{Withdrawn} \\ \text{C.} \(\begin{align*} \text{made herewith} \\ \text{D.} \(\begin{align*} \text{made previously} \end{align*} \) For B & C \(\text{See Required} \) See Required \(\text{Separate} \) (Pat-256)	Claims remaining after amendment	Highest nur previously p		Present Extra	Large/Small Entity	Additional Fee	Fee Code Lg/Sm
2. Total Effective Claims	116	**minus	126	0	x \$18/\$9 =	+ \$0	103/203
3. Independent Claims	8	***minus	8	0	x \$84/\$42 =	+ \$0	102/202
4. If amendment enters <u>proper</u> multiputime (leave <u>blank</u> if this is a <u>reissue</u> a	+ \$280/\$140 =	+ \$0	104/204				
Original due Date: May 11, 20 Retition is hereby made to extendate to cover the date this response requisite fee is attached (Usable on)	d the original d	h the (2 (3 no.OA 4	1 mo) mos) mos) mos)	\$110/\$55 = \$400/\$200 = \$920/\$460 = \$1,440/\$720= \$1,960/\$980=	+ \$0	100 A	115/215 116/216 117/217 118/218 128/228
7. Enter any previous extension fee paid since above original due date and subtract					- \$0		
8. Extension Fe					on Fee Attached	+ \$0	
9. If Terminal Disclaimer attached, add Rule 20(d) official fee					+ \$110/\$55	+ \$0	148/248
10. If IDS attached requires Official Fee under Rule 97 (c),						+ \$0	126 126
11. After-Final Request Fee per rules 129(a) and 17(r) +						+ \$0	146/246
12. No. of additional inventions for ex	x \$740/370 ea	+ \$0	149/249				
13. Request for Continued Examination (RCE)						+ \$0	1179/1279
14. Petition fee for							
15. TOTAL FEE ENCLOSED =						\$0	
16. *If the entry in this snace is less than entr	v in nevt snace the	"Present Extra	" result i	e "n"	'		

16. *If the entry in this space is less than entry in next space, the "Present Extra" result is "0'

17. **If the "Highest number previously paid for" in this space is less than 20, write "20" in this space.

18. ***If the "Highest number previously paid for" in this space is less than 3, write "3" in this space.

Our Deposit Account No. 03-3975).

	Our Deposit Au	Our Deposit Account No. 00 007 07						
	(Our Order No.	038559	0282005	i				
	•	C#	M#					
CHARGE STATEMENT: The Commissioner is	hereby authorized to charge any fee specifically authorized herea	fter, or any missing	or insufficient fe	e(s) filed, or asserted to be				
filed, or which should have been filed herewith of	or concerning any paper filed hereafter, and which may be require	d under Rules 16-1	8 (missing or ins	ufficiencies only) now or				
hereafter relative to this application and the rest duplicate copy of this sheet is attached.	ulting Official Document under Rule 20, or credit any overpayment	, to our Accounting	/Order Nos. sno	wn above, for which purpose	а			
This CHARGE STATEMENT does not author	ize charge of the <u>issue fee</u> until/unless an issue fee transmitt	al sheet is			\neg			
filed.								
	Pillsbury Winthrop LLP							
	Intellectual Property Group							
50 Fremont Street	By Atty: Karry W. Wang		Reg. No.	50,178				
P. O. Box 7880	0-16:20							
San Francisco, CA 94120-7889	CFAIGE A James VIVI		_ Fax:	(415) 983-1200				
Tel: (415) 983-1000 Max	IVFD		Tel:	(415) 983-1280				

Tel: (415) 983-1000 Atty/Sec: KWW/PDG TC 1700

ORIGINALLY FILED

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TC 1700

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: LICHTENHAN, et al.

Serial No. 09/631,892

Filed: August 4, 2000

MAY 1 3 2002

Examiner: Robertson

Art Unit: 1712

Title: PROCESS FOR THE FORMATION OF

POLYHEDRAL OLIGOMERIC SILSESQUIOXANES

AMENDMENT AND RESPONSE

Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Office Action dated April 11, 2002, please enter and consider the following amendment and remarks.

IN THE SPECIFICATION

Please replace the paragraph beginning at page 2, line 1, with the following rewritten paragraph:

--Prior art has reported that bases (e.g., NaOH, KOH, etc.) could be used to both catalyze the polymerization of POSS into lightly networked resins or to convert selected polysilsesquioxane resins into homoleptic polyhedral oligomeric silsesquioxane structures. Marsmann et al have more recently shown that a variety of bases can be used to redistribute smaller homoleptic POSS cages into larger sized homoleptic cages. (Marsmann, H.C. and Rikowski, E., Polyhedron, 1997, 16, 3357-3361). While there is precedent in the literature for treatment of silsesquioxanes and POSS systems with base, the previous art does not afford the selective manipulation of silicon-oxygen frameworks and the subsequent controlled production of POSS fragments, homoleptic POSS nanostructures. Furthermore, the prior art does not provide methods of producing POSS systems suitable for functionalization and